

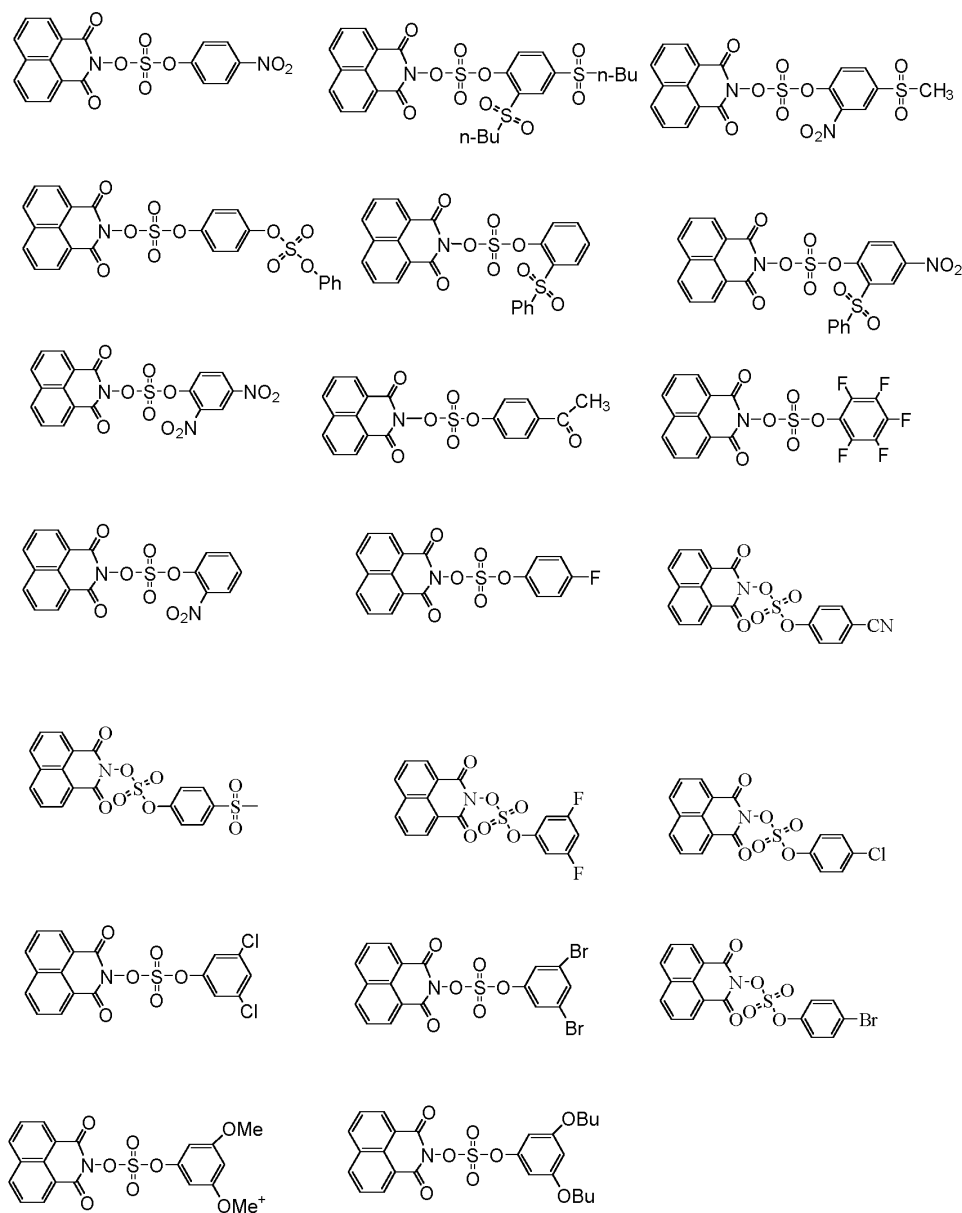


FIG. 1a

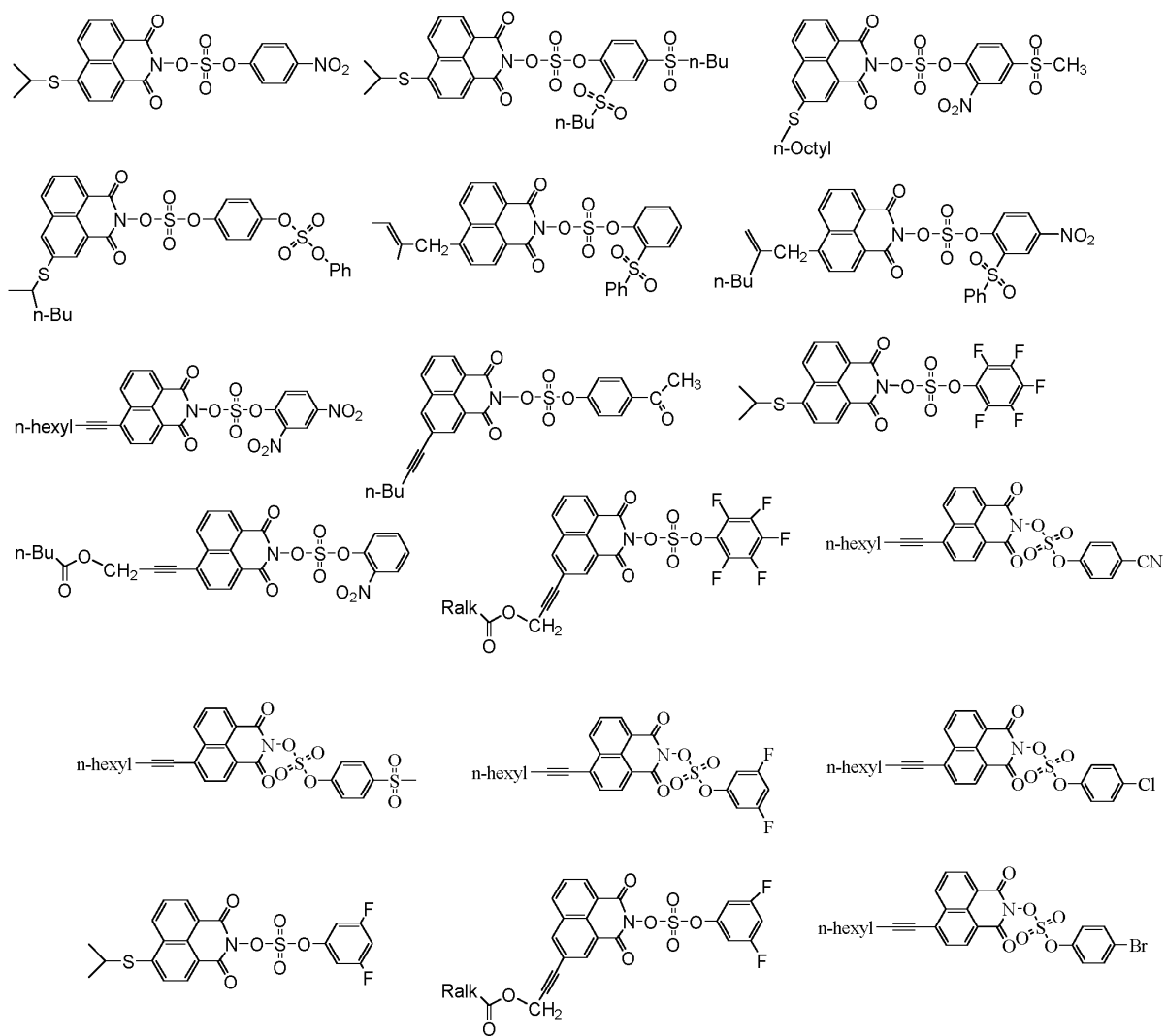


FIG. 1b

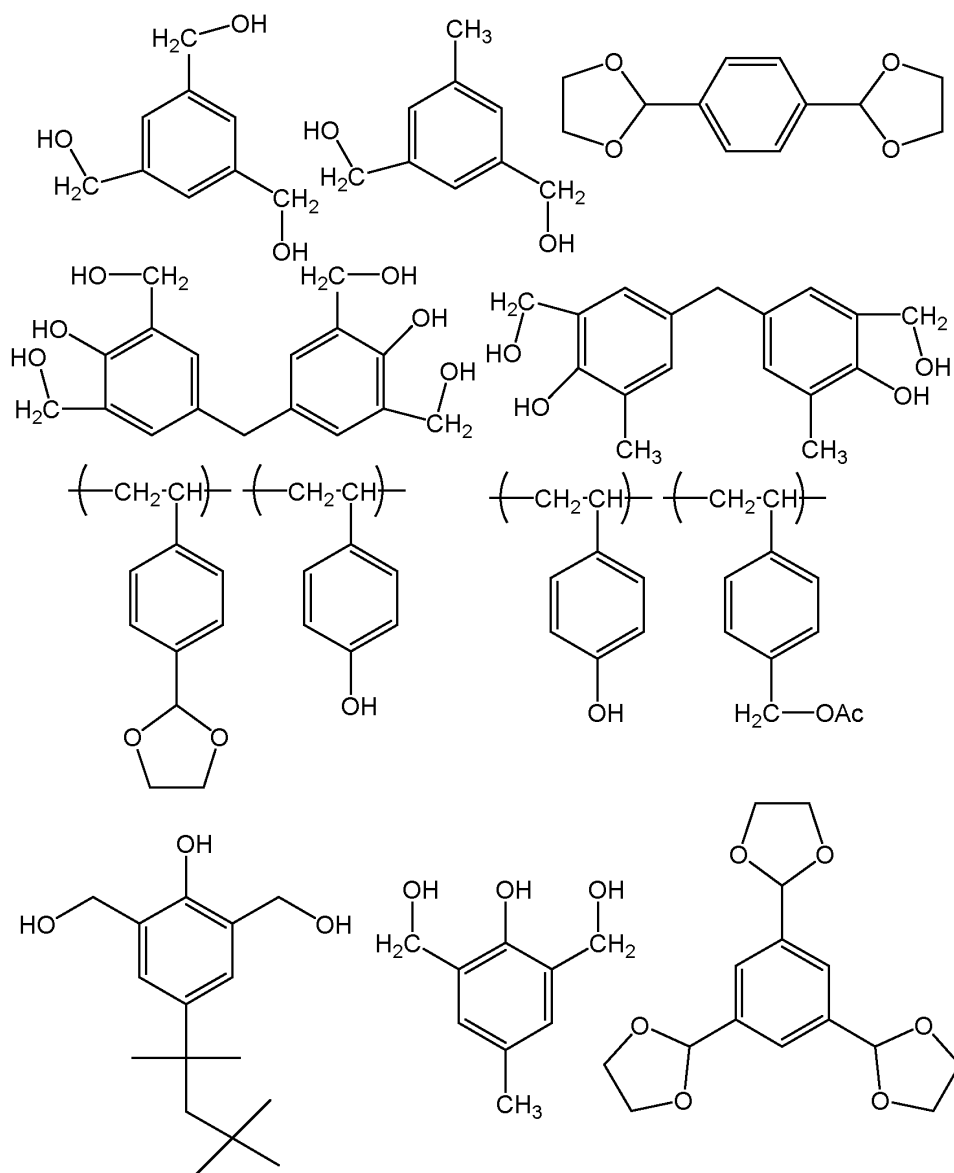


FIG. 2

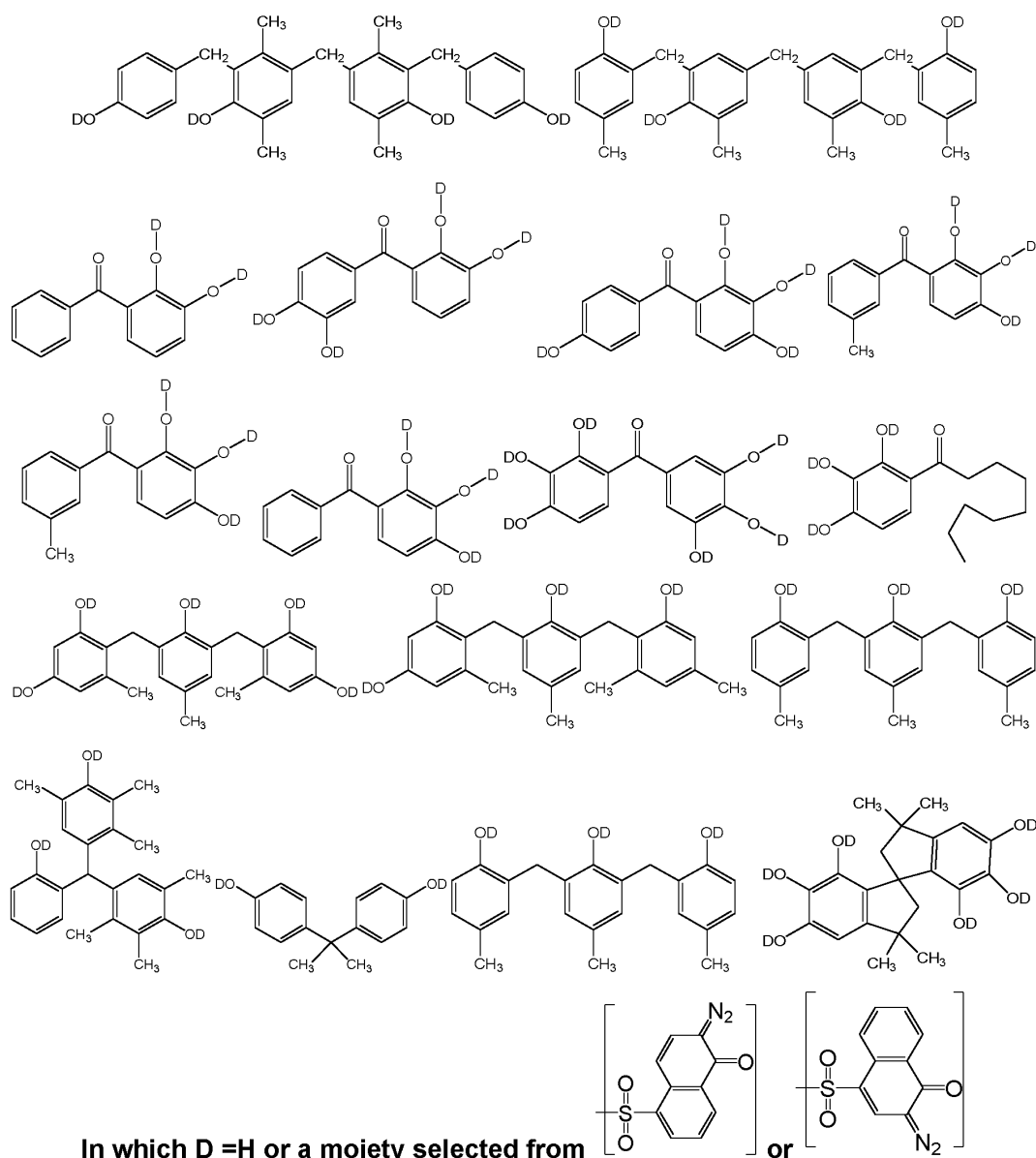


FIG. 3

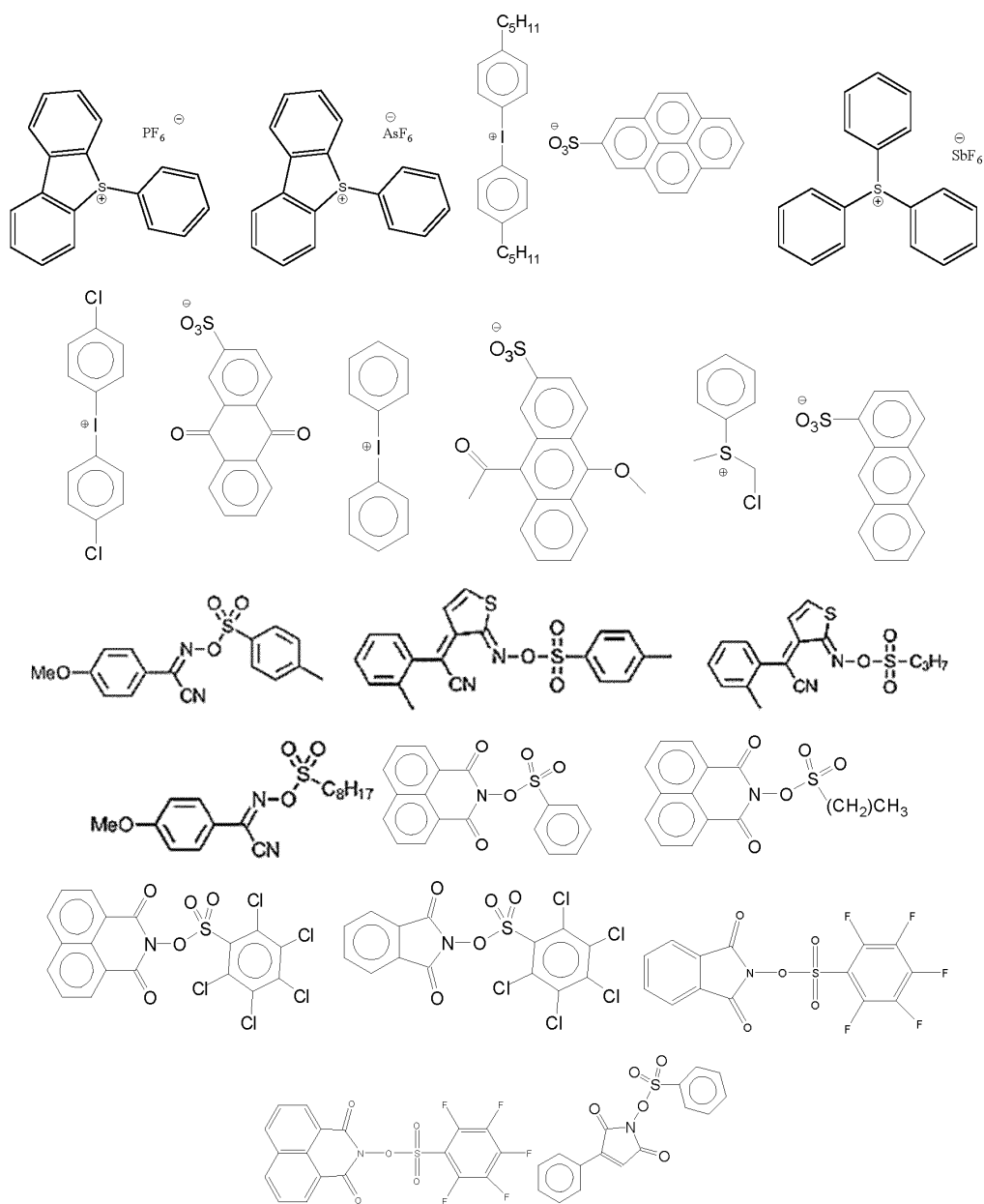


FIG. 4

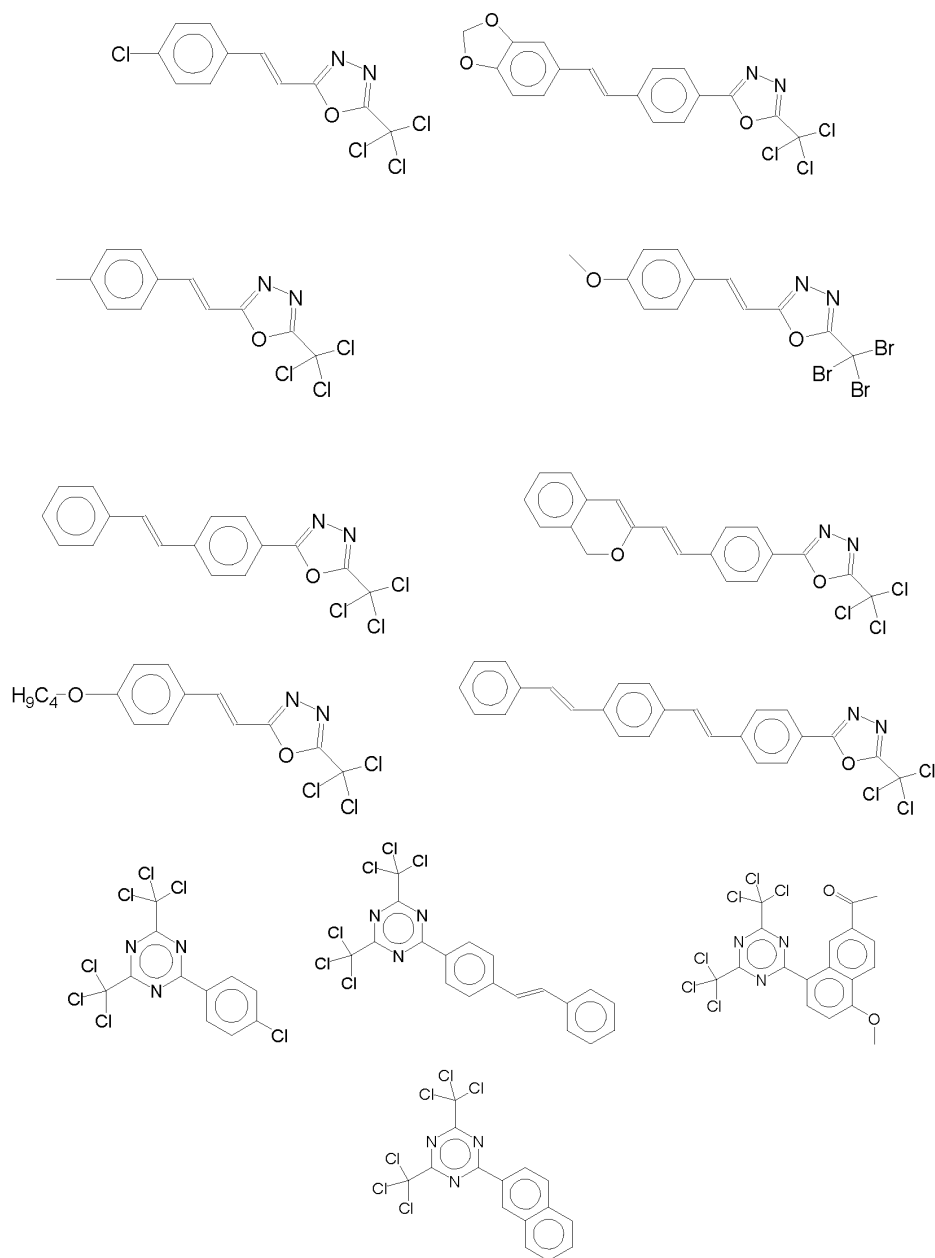


FIG. 5

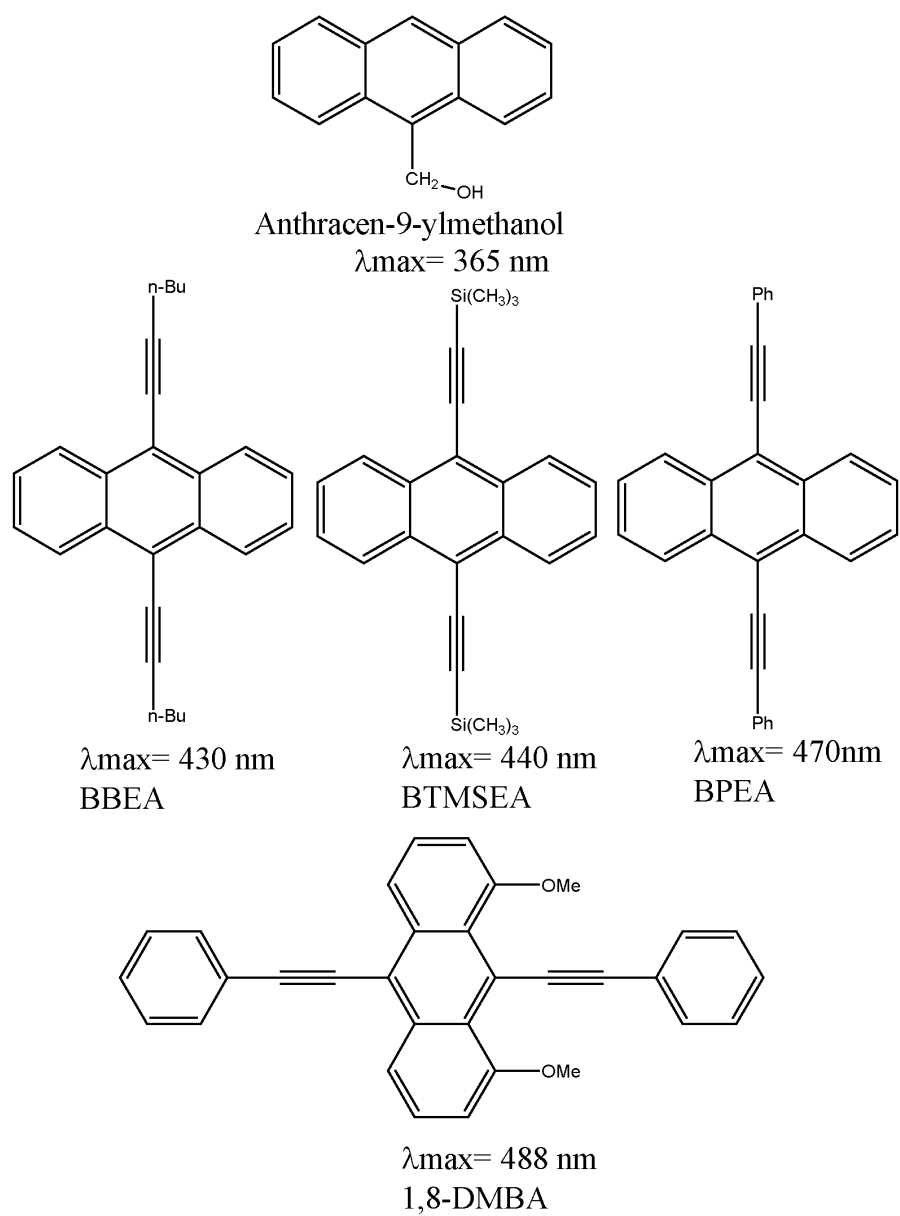


FIG. 6

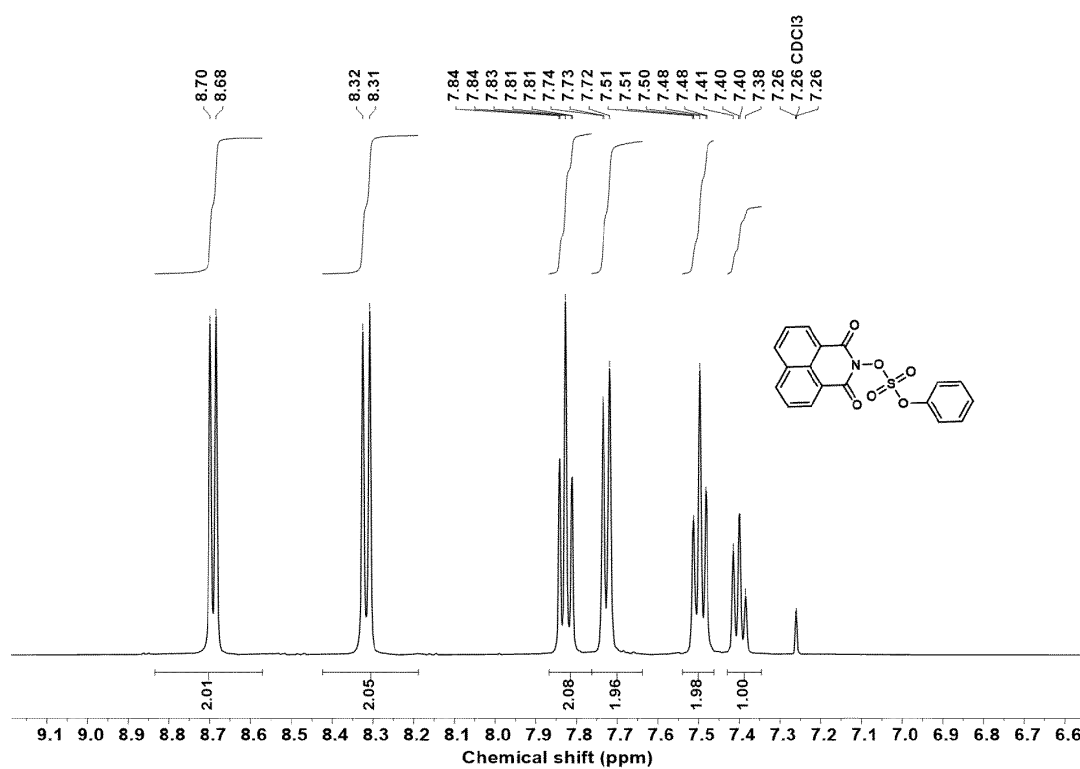


FIG. 7

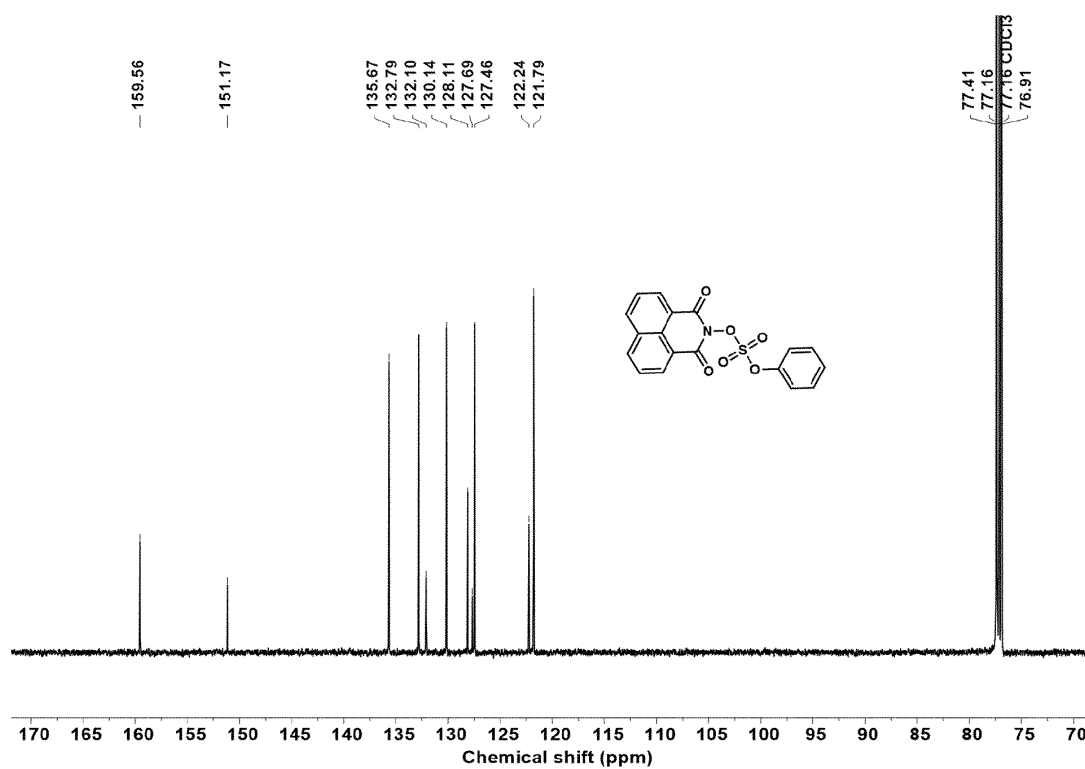


FIG. 8

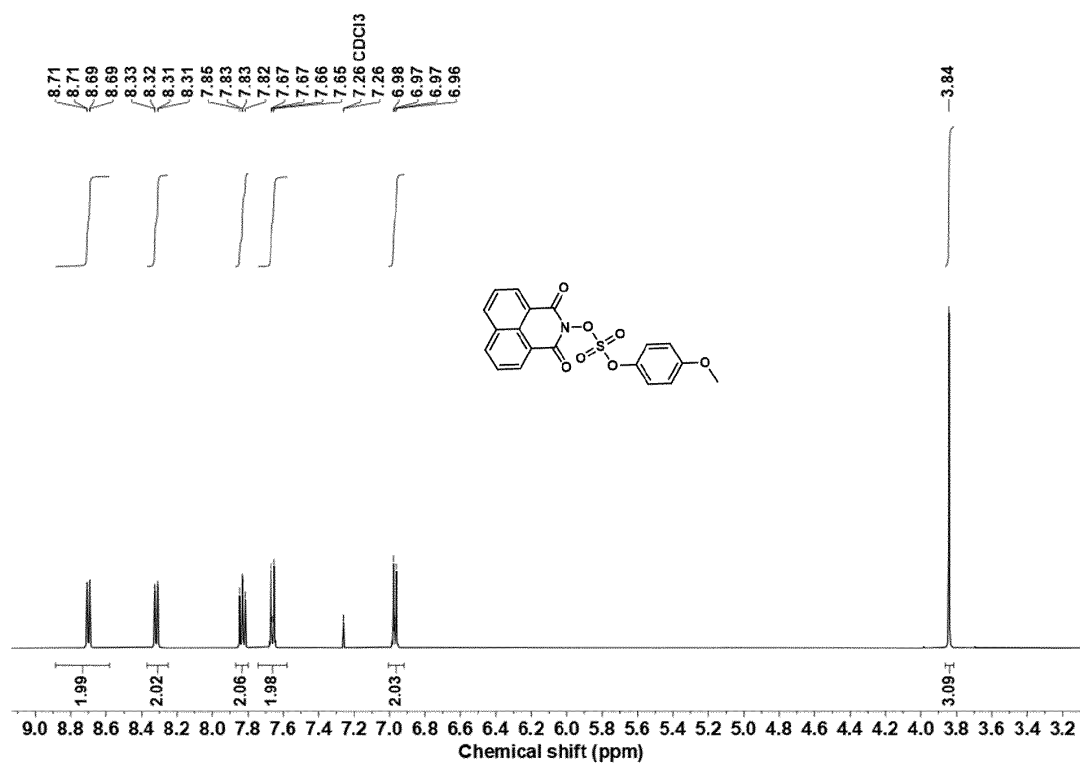


FIG. 9

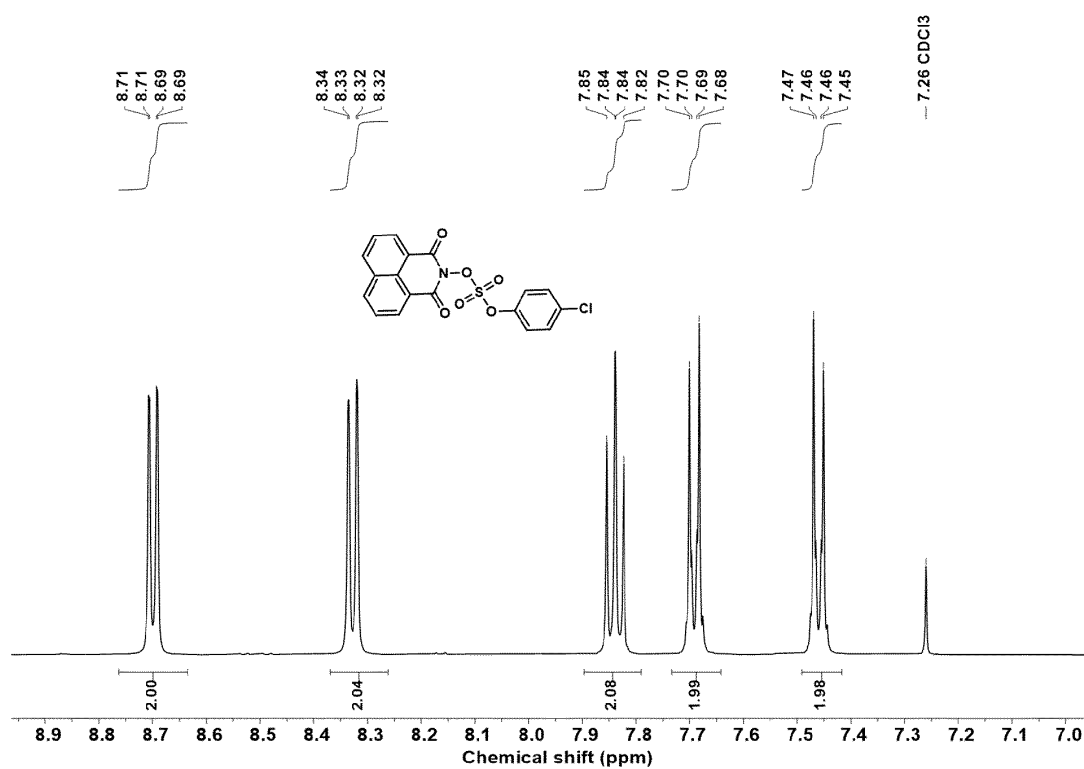


FIG. 10

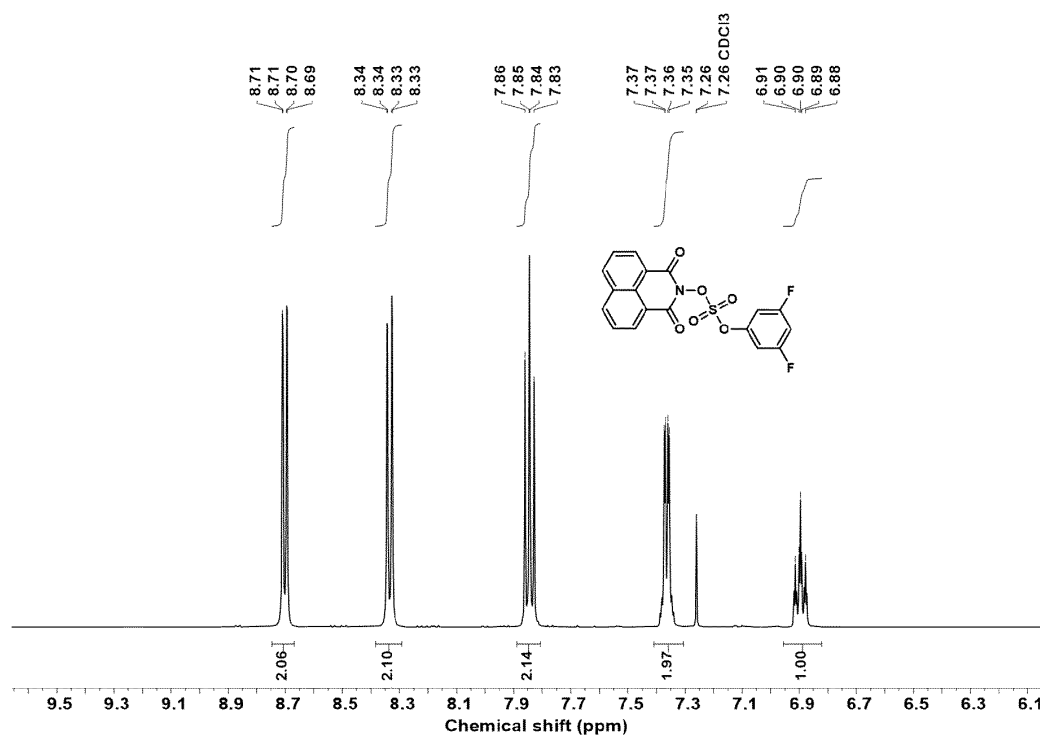


FIG. 11

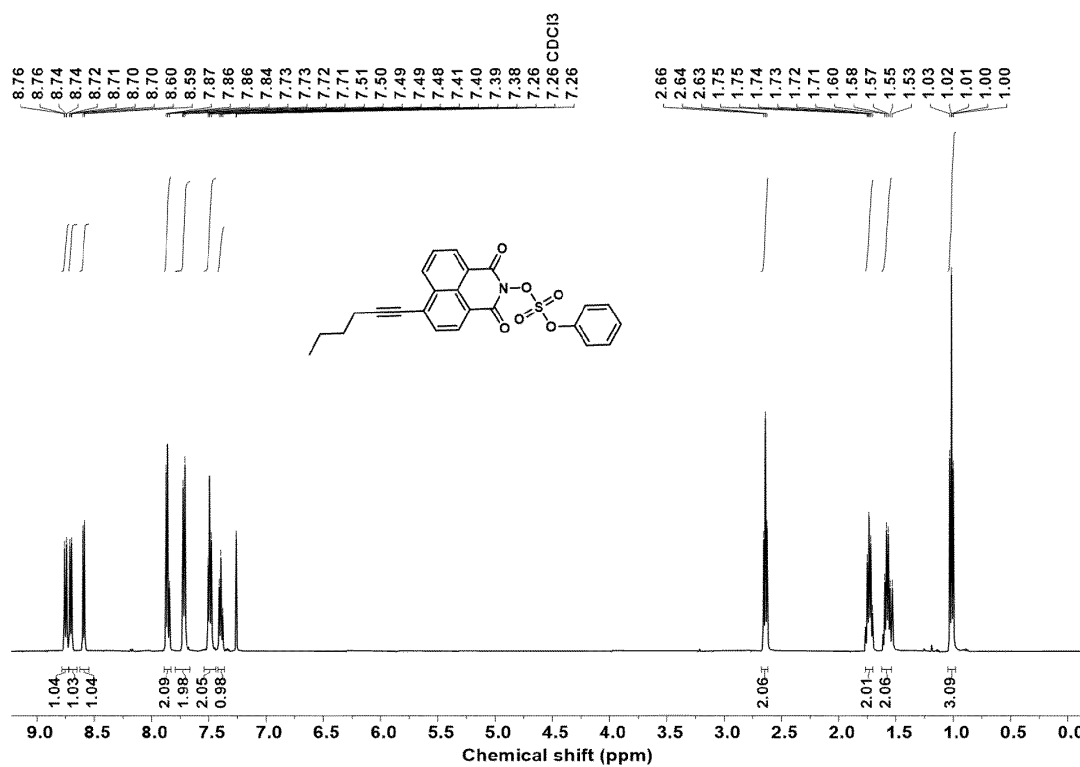


FIG. 12

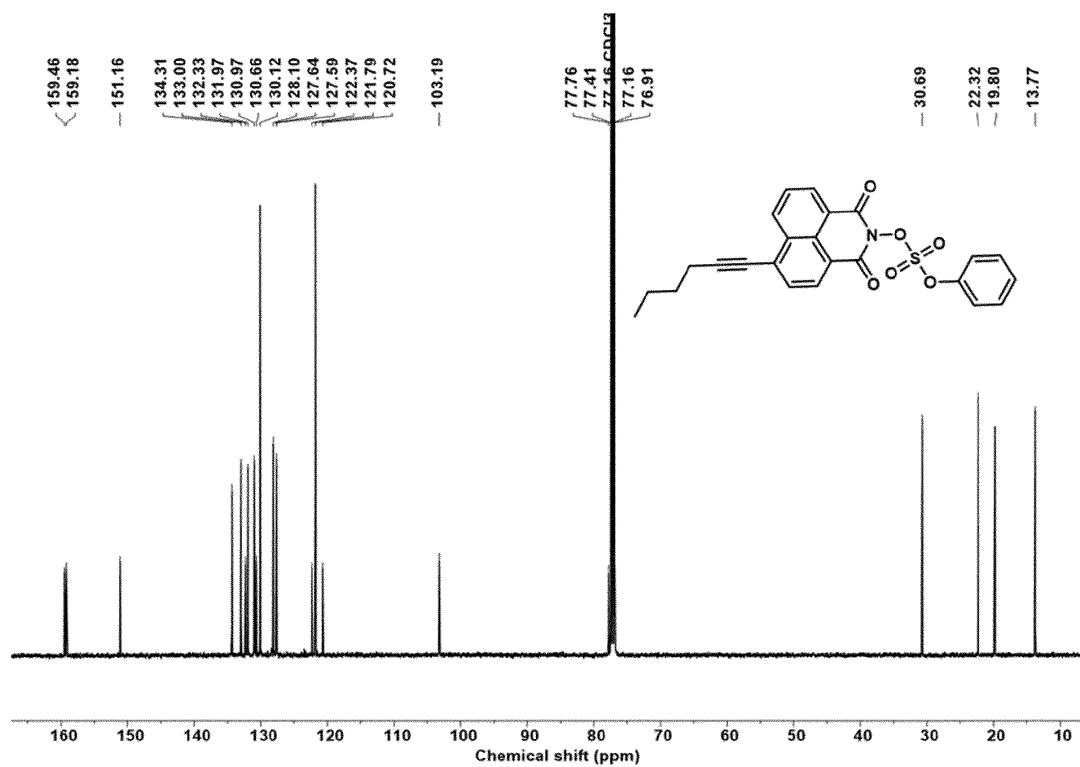


FIG. 13

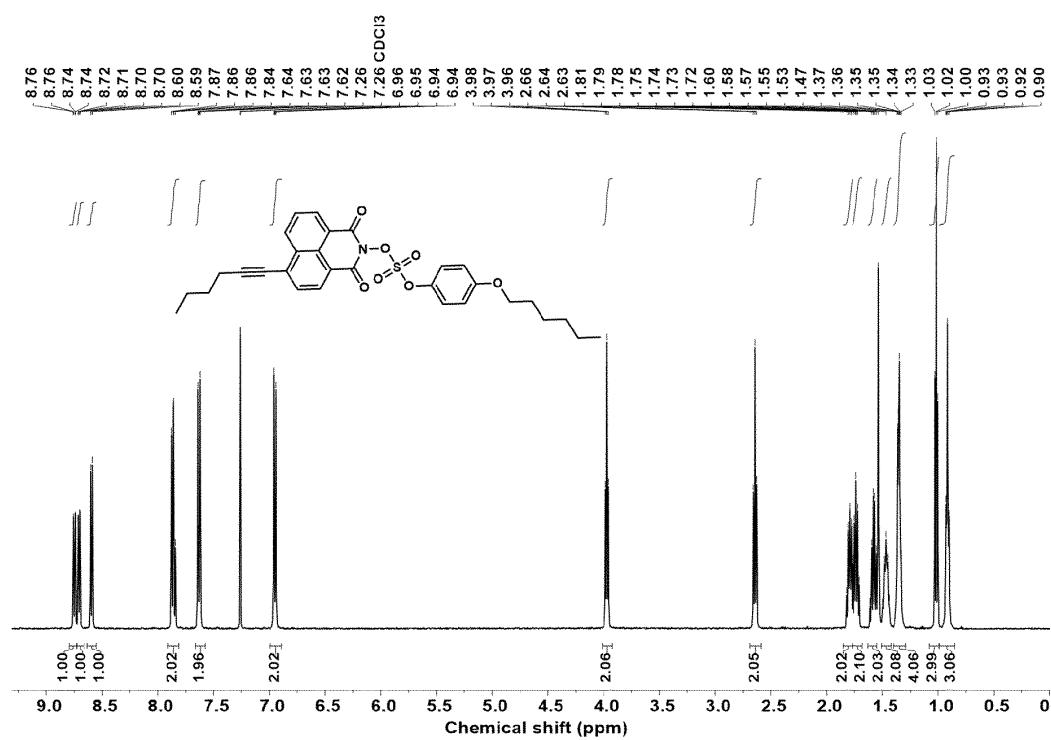


FIG. 14

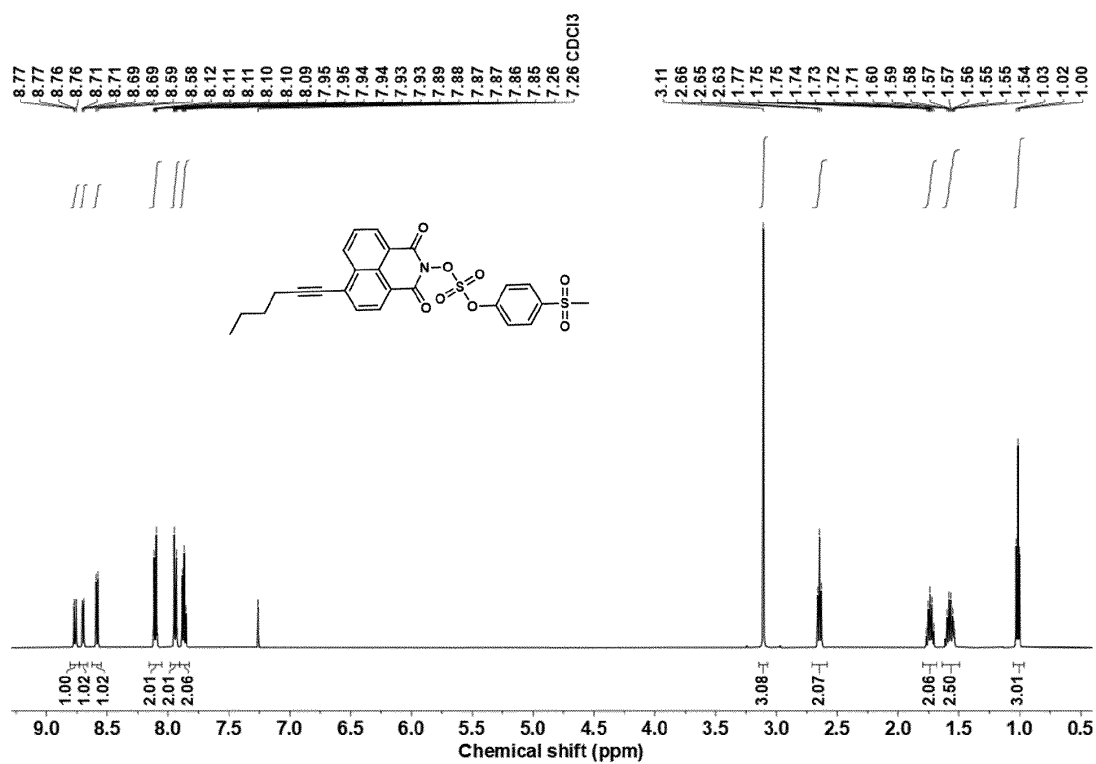


FIG. 15

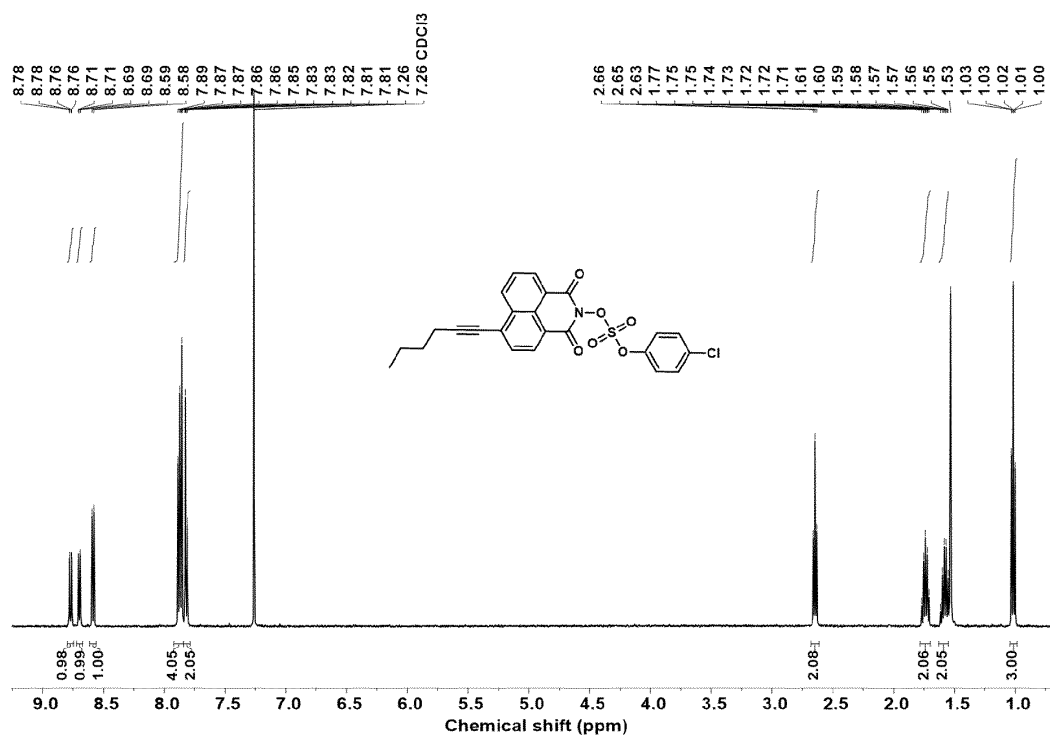


FIG. 16

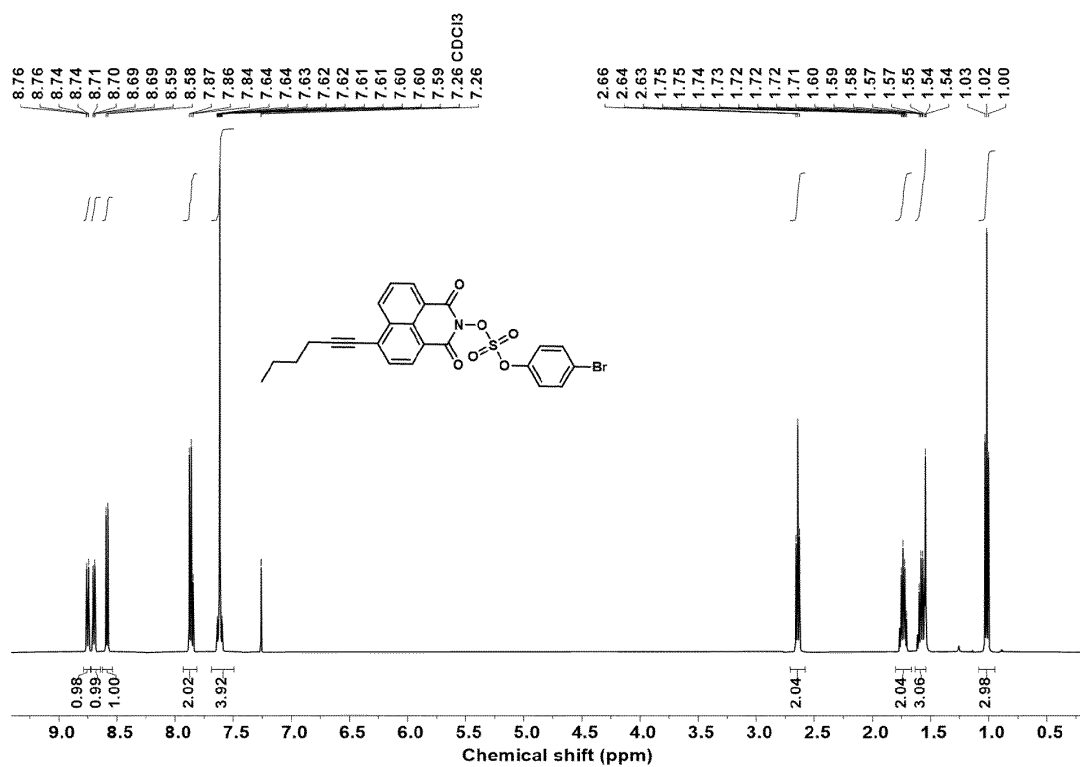


FIG. 17

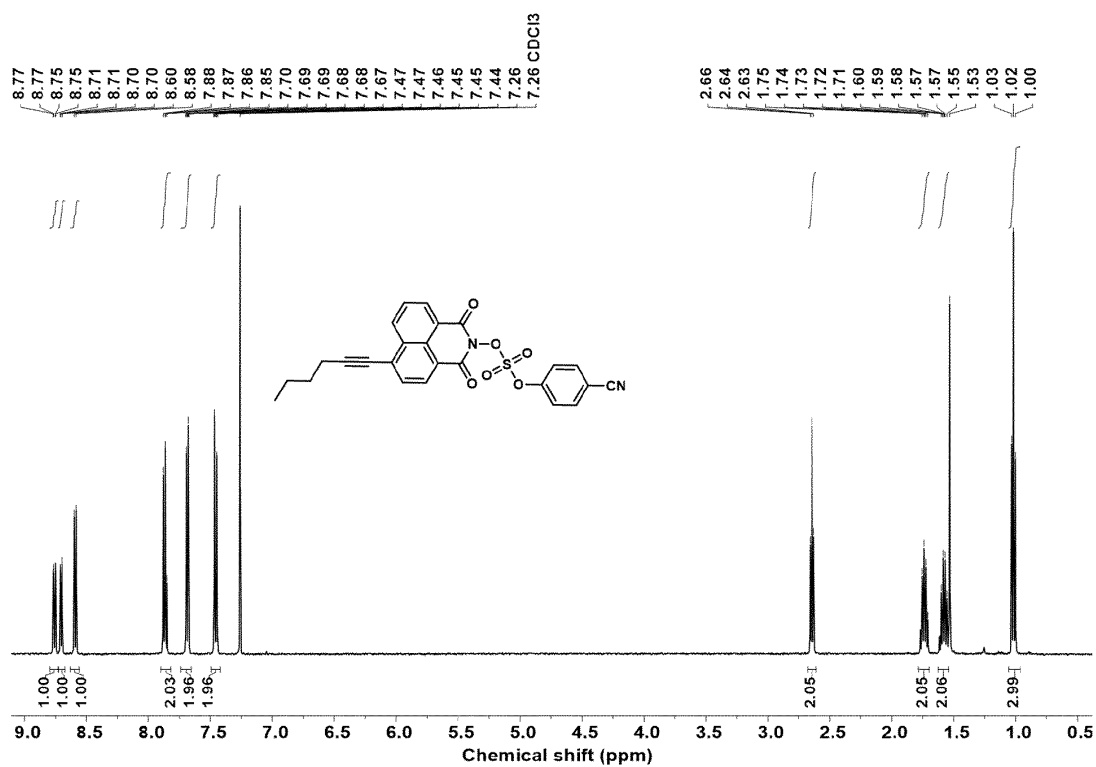


FIG. 18

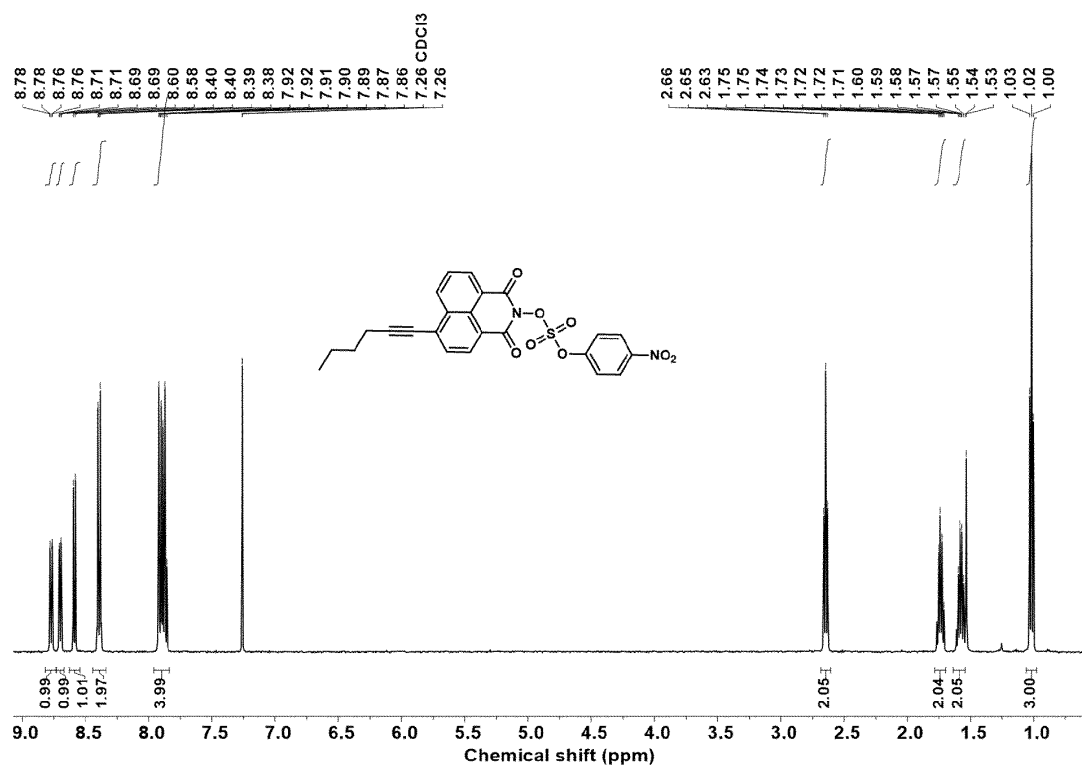


FIG. 19

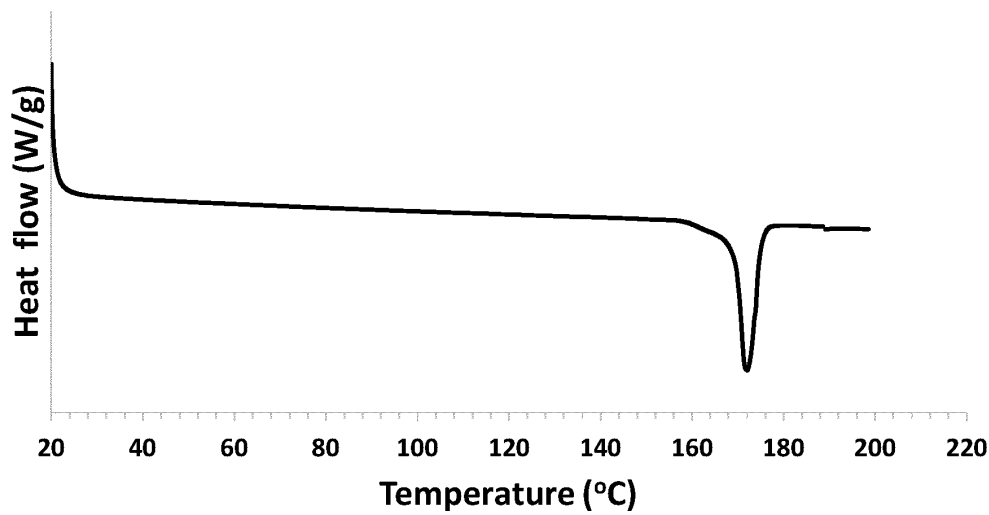


FIG. 20

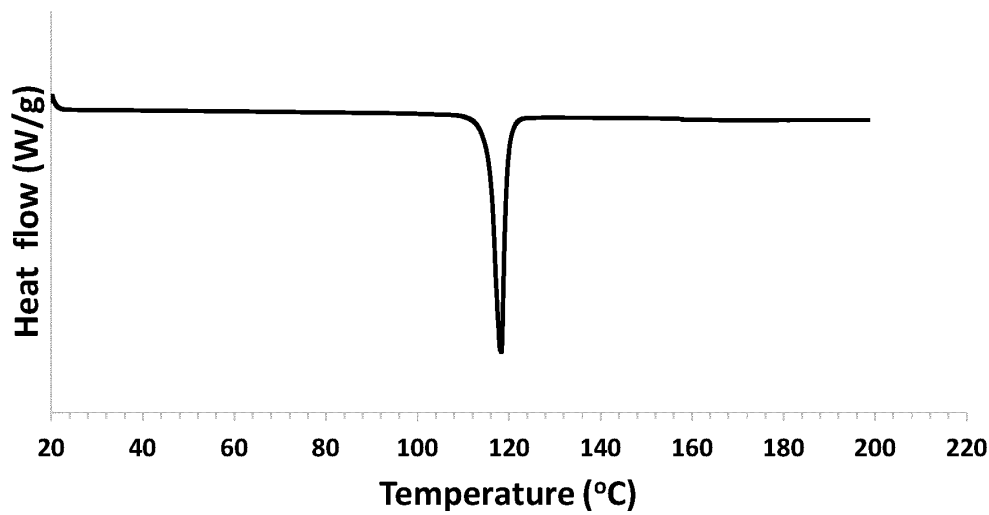


FIG. 21

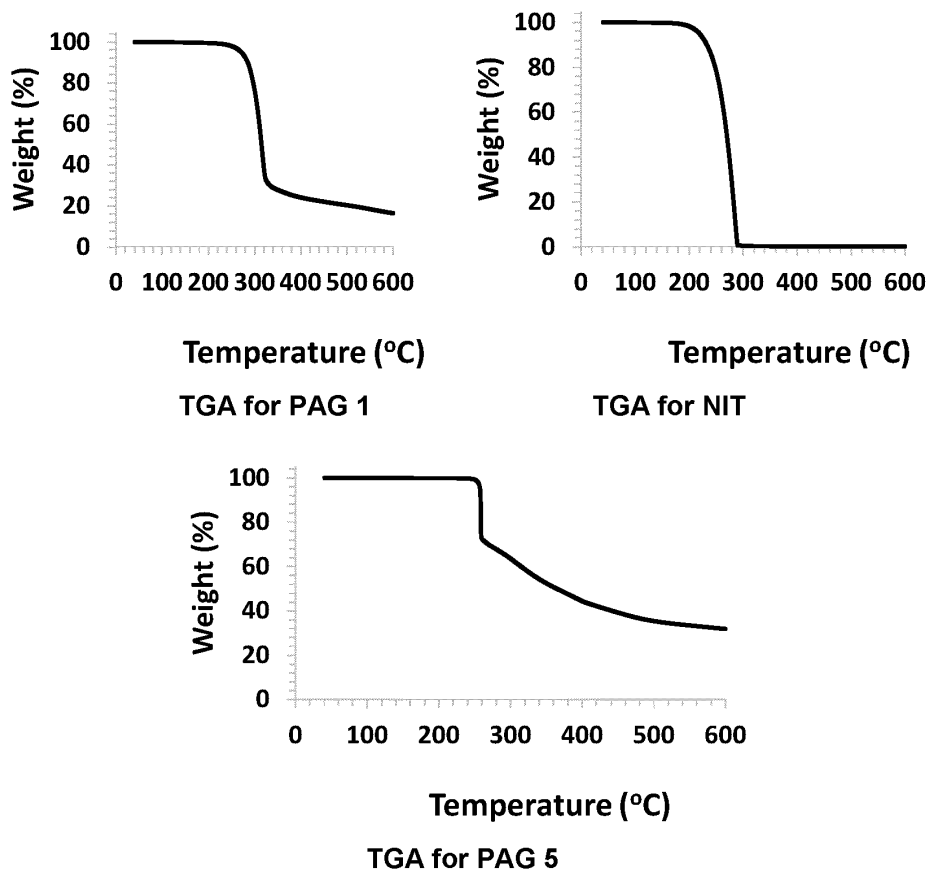


FIG. 22

Table 4 Comparison of i-line photoresist examples

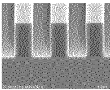
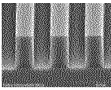
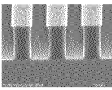
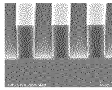
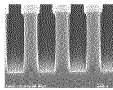
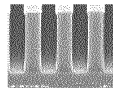
	Photo-resist Ex.1	Photo-resist Comp. Ex. 1	Photo-resist Ex. 2	Photo-resist Comp. Ex. 2	Photo-resist Ex. 4	Photo-resist Comp. Ex. 3	Photo-resist Comp. Ex. 4
i-line PAG	PAG 1	NIT	PAG 1	NIT	PAG 1	NIT	PA-298
Cross-section SEM @ 5 μm L/S (FT=10.0 μm)					 2.0 μm L/S @ 8.0 μm FT	 2.0 μm L/S @ 8.0 μm FT	n/a
Dose-to-Print (mJ/cm ²)	700	450	520	140	350	150	No lines < 10 μm was printed below 700 mJ/cm ² .

FIG. 23

Table 5 Comparison of i-line photoresist examples

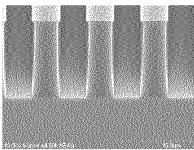
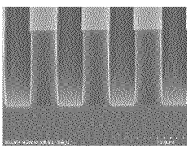
	Photo-resist Ex.6	Photo-resist Comp. Ex. 5
i-line PAG	PAG 1	NIT
Cross-section SEM @ 4 μm L/S (FT=12.0 μm)		
Dose-to-Print (mJ/cm²)	140	140

FIG. 24

Table 6 Comparison of i-line photoresist examples

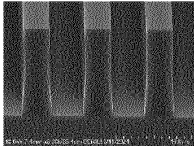
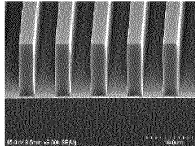
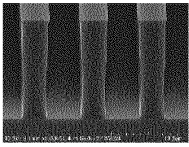
	Photo-resist Ex.8		Photo-resist Ex. 9
i-line PAG	PAG 1		PAG 10
Substrate	Si	Cu	Si
Cross-section SEM @ 4 μm L/S (FT=12.0 μm)			
Dose-to-Print (mJ/cm²)	100	155	120

FIG. 25

Table 7 Comparison of i-line photoresist examples

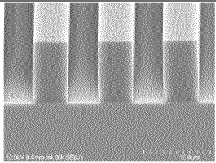
	Photo-resist Ex. 12
i-line PAG	PAG 1
Cross-section SEM @ 5 μm L/S (FT=10.0 μm)	
Dose-to-Print (mJ/cm²)	450

FIG. 26